
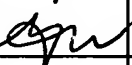
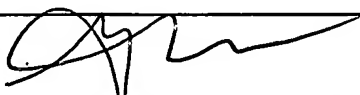
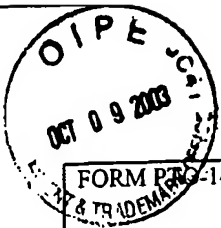




FORM PTO-1449		US Dept. of Commerce Patent and Trademark Office		ATTORNEY DOCKET NO. 643		SERIAL NO. 10/602,172	
INFORMATION DISCLOSURE STATEMENT  (use several sheets if necessary)				APPLICANT Michael B. Korzenski, et al.			
				FILING DATE June 24, 2003		GROUP	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<b>FOREIGN PATENT DOCUMENTS</b>							
		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION YES NO
							X (abstract only)
<b>OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)</b>							
	AA	Post-Etch Cleaning of 300mm Dual Damascene Low-K Dielectric Structures Using Supercritical CO <sub>2</sub> , Abs. 796, 204 <sup>th</sup> Meeting 2003 The Electrochemical Society, Inc., Robert B. Turkot, Jr., et al.					
	AB	Supercritical CO <sub>2</sub> Post-Etch Cleaning of a Patterned Porous Low-K Dielectric, Ashland Specialty Chemical Company, D. Peters, et al., pgs. 194-201.					
EXAMINER 					DATE CONSIDERED 3-30-05		
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.							



FORM PTO-1449		US Dept. of Commerce Patent and Trademark Office		ATTORNEY DOCKET NO. 643		SERIAL NO. 10/602,172	
INFORMATION DISCLOSURE STATEMENT  (use several sheets if necessary)				APPLICANT Michael B. Korzenski, et al.			
				FILING DATE June 24, 2003		GROUP	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION YES NO
							X (abstract only)
OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)							
<i>gk</i>	AA	Post-Etch Cleaning of 300mm Dual Damascene Low-K Dielectric Structures Using Supercritical CO <sub>2</sub> , Abs. 796, 204 <sup>th</sup> Meeting 2003 The Electrochemical Society, Inc., Robert B. Turkot, Jr., et al.					
<i>gk</i>	AB	Supercritical CO <sub>2</sub> Post-Etch Cleaning of a Patterned Porous Low-K Dielectric, Ashland Specialty Chemical Company, D. Peters, et al.					
EXAMINER <i>[Signature]</i>					DATE CONSIDERED 3-30-05		
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.							